

Appl. No. 09/695,814

Amendments to the Claims

Claims 1-84 (Cancelled)

85. (Currently amended) A sputtering target comprising at least 90% Zr and one or more elements selected from the group consisting of Ba, Be, Ca, Ce, Co, Cs, Dy, Er, Fe, Gd, Ho, La, Mn, Mo, Nd, Pr, Sc, Sm, Sr, V, W, and Yb; ~~the Zr being the majority element of~~ the target.

Claims 86-87. (Cancelled).

88. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is at least 94%.

89. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is at least 97%.

90. (Original) The sputtering target of claim 85 wherein the Zr concentration within the target is less than 98%.

91. (Cancelled).

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92. (Previously presented) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is in a range of 0.001% to 10% of the target.

93. (Previously presented) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 0.01% of the target.

94. (Previously presented) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 0.1% of the target.

95. (Previously presented) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 1% of the target.

96. (Previously presented) The sputtering target of claim 85 wherein the total non-zirconium metal content of the target is at least 2% of the target.

97. (Currently amended) ~~The sputtering target of claim 85~~ A sputtering target comprising Zr and one or more elements selected from the group consisting of Ba, Be, Ca, Ce, Co, Cs, Dy, Er, Fe, Gd, Ho, La, Mn, Mo, Nd, Pr, Sc, Sm, Sr, V, W, and Yb; the Zr being the majority element of the target; and further comprising one or more elements selected from the group consisting of Mg, Al, B, Hf, Nb, Ni, Ta, Y and Ti.

Claims 98-103. (Cancelled)

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104. (Currently amended) A sputtering target comprising at least 94% Ti and greater than 2% B, by weight; the Ti being the majority element of the target.

Claims 105 -107. (Cancelled)

108. (Original) The sputtering target of claim 104 wherein the Ti concentration within the target is at least 97%.

Claims 109-117 (Cancelled).

118. (Currently amended) The A sputtering target of claim 104 consisting of Ti and greater than 2 % B, by weight; the Ti being the majority element of the target.